

## Fabrication of MoS<sub>2</sub> Photodetectors for Near-Infrared Biosensing Applications

Seungjun Ki, Younggeun Park, Byunghoon Ryu, Katsuo Kurabayashi,  
and Xiaogan Liang\*

Mechanical Engineering Department, University of Michigan, Ann Arbor, MI 48109

Over the last few decades, researchers have been developing novel and high-performance diagnostic biosensors using metallic nanoparticle-based localized surface plasmon resonance (LSPR) components.[1] In these biosensing devices, photodetectors with high photoresponsivity and low internal noise level are required to detect the optical signals induced by biomarker binding events (i.e., Antigen-antibody binding). In recent years, atomically thin (i.e., 2-25 nm thick) molybdenum disulfide (MoS<sub>2</sub>) channels have been integrated with LSPR structures to enable fast and sensitive colorimetric monitoring of disease-related biomarkers.[2] However, such biosensors are mostly operated in the ultraviolet/visible wavelength regimes, which demands a purification step to separate out a variety of unwanted biological species that absorb visible lights. This process typically takes several hours, which prevent implementation of such sensors for point-of-care (POC) scenarios. Therefore, it would be imperative to develop biosensors or immunoassay tools consistent with the whole blood assay with minimal sample preparation steps.[3] To meet this goal, a systematical study on high-performance near-infrared (NIR) photoconductors is strongly motivated because most biological species in the whole blood samples have high degrees of transparency for NIR lights.

In this work, we studied the photo-response properties (i.e., Photoresponsivity spectra) of in-plane MoS<sub>2</sub> photodetectors as the function of their geometric dimensions (e.g., thickness, length, and width of photoactive layers) as well as fabrication conditions (e.g., doping, etching, and substrate choice). This work has enabled the NIR operation capabilities of plasmonic colorimetric biosensing, thereby reducing assay times and background interference.

**Fig. 1(a)** shows an as-fabricated MoS<sub>2</sub> photoconductor structure with effective channel length of ~1 μm laterally sandwiched by a pair of Ti/Au electrode pads, which secures a smooth, single-crystal-domain sensing channel structure. The optimal MoS<sub>2</sub> channel thickness has been experimentally identified to be ~14 nm. To characterize optoelectronic properties of a MoS<sub>2</sub> photodetector, photocurrent is measured at fixed source-drain voltage,  $V_{ds} = 1$  V. **Fig. 1(b)** demonstrates the photoresponsivity spectra measured from a few-layer (FL) MoS<sub>2</sub> photodetector and a 14 nm thick multilayer MoS<sub>2</sub> photodetector. The 14 nm thick MoS<sub>2</sub> channel exhibits three-fold higher photoresponsivity as compared to that of the few-layer MoS<sub>2</sub> channel (3 nm thick) within the NIR region. Up to the present time, the technological utility of multilayer MoS<sub>2</sub> has been underappreciated in comparison with monolayer and few-layer MoS<sub>2</sub>. However, our study indicates that multilayer MoS<sub>2</sub> films exhibit the higher photoresponsivity and light absorption coefficients than those of monolayer films under NIR illumination, which is attributed to the screening effect of the thicker MoS<sub>2</sub> films for unwanted interference signals from the backgrounds and complex analyte fluids. Furthermore, root mean square (RMS) noise values were measured from 3-nm thick and optimized 14 nm thick pristine MoS<sub>2</sub> photodetectors and a 14 nm thick O<sub>2</sub> plasma-treated MoS<sub>2</sub> photodetector, as shown in **Fig. 1(c)**. This comparison shows that the 15-nm thick MoS<sub>2</sub> channel exhibits 100-fold lower noise level than that of the 3 nm thick MoS<sub>2</sub> photoconductor and the O<sub>2</sub> plasma-treated 14 nm MoS<sub>2</sub> photodetector. This result can be attributed to the minimized substrate scattering effect in the larger thickness (10–20 nm) and smooth surface MoS<sub>2</sub> channel layers.

This work provides a guideline for making 2D-material-based NIR range photo-response devices implemented for the wash-free, mix-and-detection immunoassay of CEA in clinically relevant biofluids, including the whole blood.

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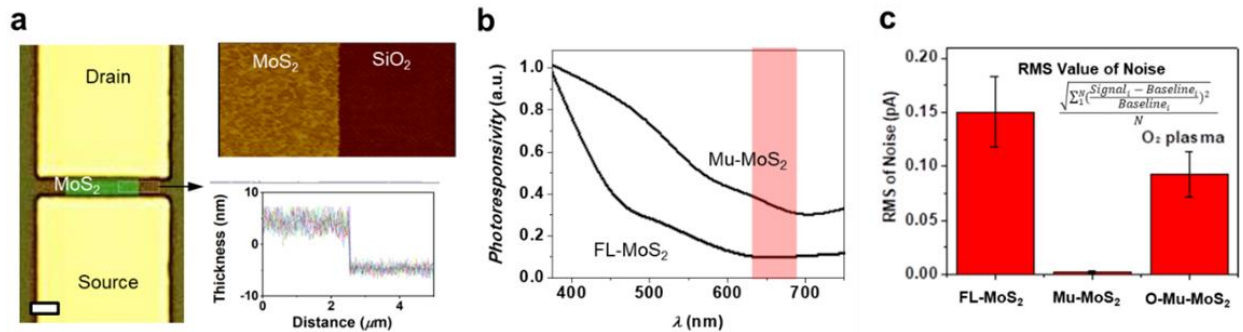


Fig. 1 MoS<sub>2</sub> photoconducting channels with different MoS<sub>2</sub> thicknesses: (a) Optical micrograph and AFM images showing the structure of a 15-nm thick MoS<sub>2</sub> channel with Ti/Au electrodes (Scale bar: 1  $\mu$ m). (b) Photoresponsivity spectrum of 15-nm thick and 3nm thick few-layer MoS<sub>2</sub> sensing channels. The photoresponsivity is given by  $R = I_{ph}/P$ , where  $I_{ph}$  is the photocurrent and  $P$  is the intensity of the incident light. (c) RMS noise values measured for pristine MoS<sub>2</sub> channels of 3 and 14 nm in thickness, and O<sub>2</sub> plasma-treated 14 nm thickness, respectively.